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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.	
10/046,330	10/25/2001	Wuwen Yi	JM32810-CIP (HO57-232)	1884	
21567	7590 07:30/2003				
WELLS ST. JOHN P.S.			EXAMINER		
601 W. FIRST SPOKANE, W	AVENUE, SUITE 1300 'A 99201	DANG, PHUC	PHUC T		
			ART UNIT	PAPER NUMBER	
			2818		
			DATE MAILED: 07/30/2003		

Please find below and/or attached an Office communication concerning this application or proceeding.

	·	Application No.	Applicant(s)	_
		10/046,330	YI ET AL.	
	Office Action Summary	Examiner	Art Unit	_
		PHUC T DANG	2818	
	The MAILING DATE of this communication app	ears on the cover shee	t with the correspondence address	_
	for Reply			
THE - Ex aft - If t - If N - Fa - An	HORTENED STATUTORY PERIOD FOR REPLY MAILING DATE OF THIS COMMUNICATION. tensions of time may be available under the provisions of 37 CFR 1.1: er SIX (6) MONTHS from the mailing date of this communication. The period for reply specified above is less than thirty (30) days, a reply 40 period for reply is specified above, the maximum statutory period valure to reply within the set or extended period for reply will, by statute by reply received by the Office later than three months after the mailing ned patent term adjustment. See 37 CFR 1.704(b).	36(a). In no event, however, ma y within the statutory minimum of will apply and will expire SIX (6) h , cause the application to becom	y a reply be timely filed thirty (30) days will be considered timely. MONTHS from the mailing date of this communication. BABANDONED (35 U.S.C. § 133).	
1)⊠	Responsive to communication(s) filed on 29 h	Mav 2003 .		
2a)[is action is non-final.		
3)[,—		natters, prosecution as to the merits is	
Dienos	closed in accordance with the practice under ition of Claims	Ex parte Quayle, 1935	C.D. 11, 453 O.G. 213.	
•	Claim(s) <u>1-30</u> is/are pending in the application	1		
7/2	4a) Of the above claim(s) is/are withdraw			
5)⊠				
6)⊠	Claim(s) <u>1-6</u> is/are rejected.			
7)□	Claim(s) is/are objected to.			
8)[Claim(s) are subject to restriction and/o	r election requirement.		
Applica	tion Papers			
, —	The specification is objected to by the Examine			
10)⊠	The drawing(s) filed on 25 October 2001 is/are:			
441	Applicant may not request that any objection to the		eyance. See 37 CFR 1.85(a). disapproved by the Examiner.	
11)	The proposed drawing correction filed on If approved, corrected drawings are required in rep		J disapproved by the Examiner.	
12)	The oath or declaration is objected to by the Ex			
•	under 35 U.S.C. §§ 119 and 120			
•	Acknowledgment is made of a claim for foreign	n priority under 35 U.S.	C. § 119(a)-(d) or (f).	
•	(i) All b) Some * c) None of:			
	1. Certified copies of the priority documents	s have been received.		
	2. Certified copies of the priority document	s have been received i	n Application No	
*	3. Copies of the certified copies of the prior application from the International Bu See the attached detailed Office action for a list	reau (PCT Rule 17.2(a)) .	
14)[Acknowledgment is made of a claim for domesti	C. § 119(e) (to a provisional application).		
15)	 a) The translation of the foreign language pro- Acknowledgment is made of a claim for domesting 			
Attachme	ent(s)			
2) 🔲 No	tice of References Cited (PTO-892) tice of Draftsperson's Patent Drawing Review (PTO-948) ormation Disclosure Statement(s) (PTO-1449) Paper No(s) _	5) Notice	ew Summary (PTO-413) Paper No(s) of Informal Patent Application (PTO-152)	

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DETAILED ACTION

Oath/Declaration

1. The oath/declaration filed on October 28, 2001 is acceptable.

Specification

2. The specification has been checked to the extent necessary to determine the presence of all possible minor errors. However, the applicant's cooperation is requested in correcting any errors of which applicant may become aware in the specification.

Claim Rejections - 35 USC § 103

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

This application currently names joint inventors. In considering patentability of the claims under 35 U.S.C. 103(a), the examiner presumes that the subject matter of the various claims was commonly owned at the time any inventions covered therein were made absent any evidence to the contrary. Applicant is advised of the obligation under 37 CFR 1.56 to point out the inventor and invention dates of each claim that was not commonly owned at the time a later invention was made in order for the examiner to consider the applicability of 35 U.S.C. 103(c) and potential 35 U.S.C. 102(f) or (g) prior art under 35 U.S.C. 103(a).

3. Claims 1-6 are rejected under 35 U.S.C. 103(a) as being unpatentable over Lauth et al. (U.S. Patent No. 5,559,065).

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Regarding claims 1-6, Lauth et al. teach a non-magnetic physical vapor deposition consisting essentially of Co or Ni and silicon [col. 1, lines 1-col. 5, lines 24].

Lauth et al. disclose all the features of the claimed invention as discussed above, but do not disclose one phase is applied in the process of Co or Ni and silicon target.

One phase is applied in the process of Co or Ni and silicon target is considered to be obvious in variation design, since any sputtering target used to define the time as the wafer stays in the furnace at high temperature. Thus, it would have been obvious to one skilled in the art to use one phase of Co or Ni and silicon in the process for a purpose of preventing defects on the silicon wafer.

Allowable Subject Matter

4. Claims 7-30 would be allowed.

The following is a statement of reason for the indication of allowable subject matter:

Claims 7-30 are considered allowable since the prior art of record and the considered pertinent to the applicant's disclosure does not teach or suggest the claimed invention. Hu et al. (U.S. Patent No. 5,763,923) do not teach the claimed invention having one phase comprising cobalt, and not more than 1% of any additional phases comprising cobalt other than one phase as recited in claim 7 and one phase comprising nickel, and not more than 1% of any additional phases comprising nickel other than one phase as recited in claim 16 and one phase comprising the one or more of Co, Ni, Ta, Ti, Pt, and Mo and not more than 1% of any additional phases comprising the one or more of Co, Ni, Ta, Ti, Pt and Mo other than the one phase; wherein the target is non-magnetic as recited in claim 22 and one phase comprising WSi₂ and not more than 1% of any

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additional phases other than one phase; and wherein the target is non-magnetic as recited in claim 29.

Conclusion

- Any inquiry concerning this communication or earlier communications from the 5. examiner should be directed to Phuc T. Dang whose telephone number is 703-305-1080. The examiner can normally be reached on 8:00 am-5:00 pm.
- If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, David C. Nelms can be reached on 703-308-4910. The fax phone numbers for the organization where this application or proceeding is assigned are 703-308-7722 for regular communications and 703-308-5841 for After Final communications.
- Any inquiry of a general nature or relating to the status of this application or 7. proceeding should be directed to the receptionist whose telephone number is 703-308-PP Jangrinu 0956.

Phuc T. Dang

Examiner

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July 15, 2003